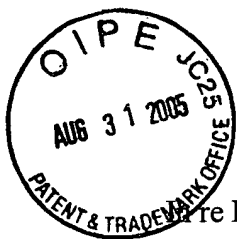


CoFC

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Under Patent of:

Examiner: H. Nguyen

Group Art Unit: 2851

August 31, 2005

METHOD THEREFOR, SEMICONDUCTOR DEVICE:
MANUFACTURING METHOD USING THE)
APPARATUS, AND SEMICONDUCTOR :
MANUFACTURING FACTORY)

Issued: May 10, 2005

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450
Attention: Certificate of Correction Branch

Certificate
SEP 02 2005
of Correction

REQUEST FOR
CERTIFICATE OF CORRECTION
UNDER RULES 322 AND 323

Sir:

Patentee requests that a Certificate of Correction be issued by the Patent and Trademark Office due to errors which appear in the printed patent as a result of U.S. Patent and Trademark Office mistakes and mistakes of a minor nature which are not the fault of the Patent and Trademark Office.

Accompanying this letter is a check for \$100.00 to cover the statutory fee for such Certificate of Correction. Any additional fee required by this paper may be charged to Deposit Account No. 06-1205.

Patentee's undersigned attorney may be reached in our Washington, D.C. Office by telephone at (202) 530-1010. All correspondence should continue to be directed to our below-listed address.

Respectfully submitted,

A handwritten signature in black ink, appearing to read "Steven E. Warner", is written over a horizontal line.

Attorney for Patentee
Steven E. Warner
Registration No. 33,326

FITZPATRICK, CELLA, HARPER & SCINTO
30 Rockefeller Plaza
New York, New York 10112-3801
Facsimile: (212) 218-2200
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UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 6,891,593 B2

DATED : May 10, 2005

INVENTOR(S): Kiyoshi ARAKAWA

Page 1 of 3

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

ON THE COVER PAGE:

In item "(56) **References Cited**," under "OTHER PUBLICATIONS," the listed article, "Okabe, Hideo. "Photochemistry of Small Molecules," *A Wiley-Interscienc Puboication*, 1978, p. 178." should read -- Okabe, Hideo. "Photochemistry of Small Molecules," *A Wiley-Interscience Publication*," 1978, p. 178. --

In item "(57) **ABSTRACT**," cancel the current abstract and insert the following therefor:

-- An exposure apparatus includes a reticle stage which holds a reticle, a projection optical system which projects a pattern of the reticle onto a substrate, and a reticle surface plate, which is a base plate disposed between the reticle and the projection optical system and which supports the reticle stage. The reticle surface plate has an opening for transmitting exposure light. The exposure apparatus further includes a sheet glass set on the reticle surface plate so as to separate a space inside the opening of the reticle surface plate from a space above the reticle surface plate. --

MAILING ADDRESS OF SENDER:

PATENT NO. 6,891,593 B2

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PATENT NO. : 6,891,593 B2

DATED : May 10, 2005

INVENTOR(S): Kiyoshi ARAKAWA

Page 2 of 3

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

COLUMN 1:

Line 37, "recently" should be deleted.
Line 39, "have" should read -- have recently --.
Line 57, "cm⁻" should read -- cm⁻¹. --.
Line 58, "1." should be deleted.

COLUMN 2:

Line 42, the first occurrence of "an" should read -- and --.

COLUMN 6:

Line 12, "&" should read -- and --.

COLUMN 7:

Line 66, "inert" should read -- an inert --.

COLUMN 8:

Line 12, "in the" should read -- on the --.
Line 47, "&" should read -- and --.

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PATENT NO. : 6,891,593 B2

DATED : May 10, 2005

INVENTOR(S): Kiyoshi ARAKAWA

Page 3 of 3

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

COLUMN 10:

Line 20, "like" should read -- as in --.

COLUMN 11:

Line 27, "as." should read -- gas. --.

Following line 37, insert as a new paragraph -- <Embodiment of Semiconductor Production System> --.

Line 40, "micromachine" should read -- micromachine, --.

Line 56, the first occurrence of "apparatus," should read -- apparatus, a planarization apparatus, and the like) and post-process apparatuses (assembly apparatus, --.

COLUMN 14:

Line 21, "prevents a" should read -- prevents --.

Line 30, the second occurrence of "beam" should read -- beam. A sufficient transmittance and stability of the ArF excimer laser beam or fluorine (F₂) excimer laser beam --.

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